Gaussian Mixture 2021: Time-series learning and its applications in manufacturing fields



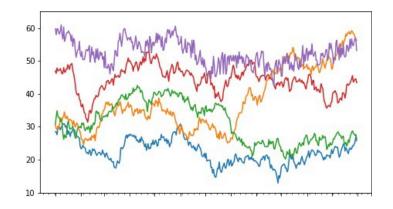
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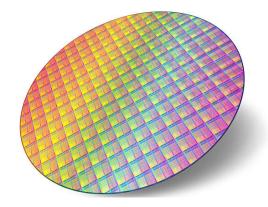
Today

- Why time-series machine learning for manufacturing AI?
- Time-series machine learning (ML)
 - what is time-series?
 - supervised and unsupervised learnings
- Difficulties with time-series ML in manufacturing
 - data challenge
 - domain knowledge critical, off-the-shelf algorithm not working
- Time-series ML applications
 - virtual metrology (VM), yield prediction and analysis, root cause analysis
- Gauss Labs success story: Virtual Metrology
 - 10x changes possible!

Why time-series ML?

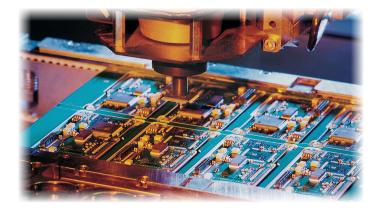
- (almost) all the data coming from manufacturing environment are time-series data
 - sensor data, process times, material measurement, equipment maintenance history, images, *etc.*
- sheer amount of time-series data is huge
 - peta-scale data per day in semiconductor manufacturing lines

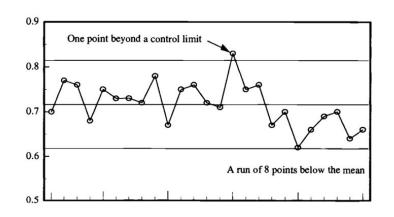




Why time-series ML?

- manufacturing application is about one of the following:
 - prediction of time-series values virtual metrology, yield prediction
 - anomaly detection on time-series data root cause analysis, yield analysis
 - classification of time-series values equipment anomaly alarm generation
 - process control with feedback advanced process control
 - metrology and inspection automatic features measurement and defect inspection
 - process time estimation or prediction planning, scheduling, dispatching





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ML techniques for time-series data

Time-series data

• definition of times-series:

$$x: T \rightarrow \mathbf{R}^n$$
 where $T = \{\ldots, t_{-2}, t_{-1}, t_0, t_1, t_2, \ldots\} \subseteq \mathbf{R}$

• example: material measurements: when n = 3

$$x(t) = \begin{bmatrix} average_thickness(t) \\ refractory_index(t) \\ image_feature_size(t) \end{bmatrix}$$

• for supervised learning, we define two time series

$$x: T \to \mathbf{R}^n$$
 and $y: T \to \mathbf{R}^m$

Supervised and unsupervised learning for time-series

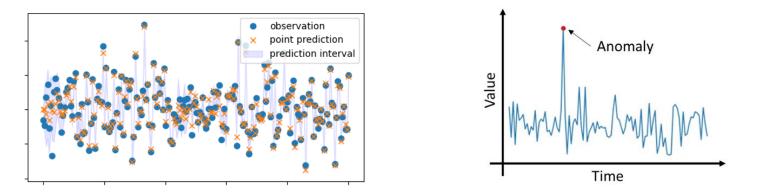
• supervised time-series learning

predict
$$y(t_k)$$

given $x(t_k), x(t_{k-1}), \ldots$ and $y(t_{k-1}), y(t_{k-2}), \ldots$

- unsupervised time-series anomaly detection
 - find time segment that is considerably different from the rest

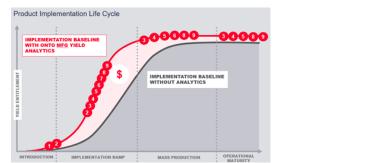
find k^* such that $x(t_k)|_{k=k^*}^{k^*+l}$ is significantly different from $x(t_k)|_{k=-\infty}^{\infty}$

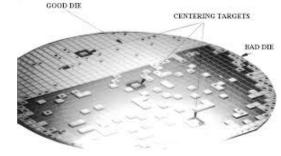


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Time-series ML applications

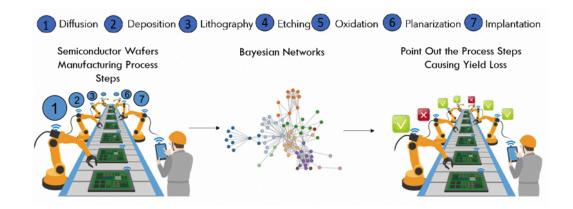
- virtual metrology
 - measure unmeasured process materials using equipment signals and other information
 - supervised learning
 - * $x(t_k)$: sensor signals, $y(t_k)$: measurement
- yield prediction
 - predict yield (# working dies / # total dies) with material measurements from equipments
 - supervised learning
 - $* x(t_k)$: material measurement in process, $y(t_k)$: yield





Anomaly detection on time-series data

- equipment alarm root cause analysis
 - when alarm goes off, find responsible equipment
 - anomaly detection
 - * $x_e(t_k)$: processed material measurement for equipment e
- yield analysis
 - find responsible equipment for yield drop



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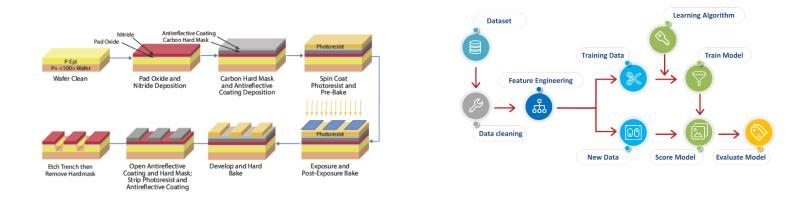
Difficulties with time-series ML in manufacturing

Data challenge

- concept drift/shift exist:
 - $p(x(t_k), x(t_{k-1}), \ldots)$ changes over time
 - $p(y(t_k)|x(t_k), x(t_{k-1}), \ldots, y(t_{k-1}), y(t_{k-2}), \ldots)$ changes over time
- hence, we have fat data, *i.e.*, # features far larger than # data
- (sometimes) poor data quality, *e.g.*, lots of missing values and incorrectly measured values
- huge volume of data to process, different types of data, high process speed demanded!

Domain knowledge and fully home-grown algorithms

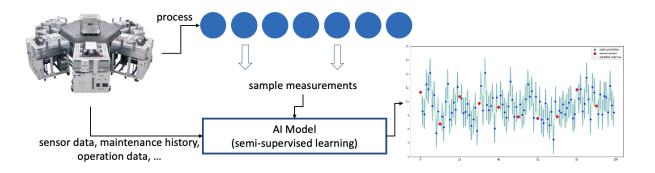
- in most cases, domain knowledge is critical!
 - close collaboration with customers required
- off-the-shelf algorithms not working!
 - developing fully customized algorithms needed



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Gauss Labs success story: Virtual Metrology (VM)

- in many cases, we cannot measure all processed materials for fundamental reasons
 - measurement equipment is too expensive
 - measuring every materials hinders production speed inducing low throughput
- thus, we do sampling (with very low smapling rate)
 - in semiconductor manufacturing line, avarage sampling rate is less than 1%
- problem: *predict the measurement of unmeasured material* using indirect signals such as sensor data, maintenance history, operation data, . . .



10x change VM makes

- background (to our best knowledge)
 - no org. has even been successful with VM (due to data challenge)
- Gauss Labs VM
 - uses fully customized online learning to cope with data drift/shift
 - RMSE error comparable to measurement equipment precision
 - also predicts uncertainty of predictions providing prediction reliability information
- VM implications
 - measuring ALL wafers equivalent to investing on 100× measurement equipment
 - enables optimal re-allocation of limited measurement resources

Conclusion

- supervised and unsupervised ML for time-series occur everywhere in industrial AI applications
- lots of challenges
 - data challenge, domain knowledge required, need for customizing algorithms
- 10x changes potentially made via various applications
 - Gauss Labs has success stories include
 - * Virtual Metrology (VM)
 - * Subnanometer-precision Machine Vision